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(21) International Application Number: PCT/EP99/09446 (22) International Filing Date: 3 December 1999 (03.12.99) (30) Priority Data: 09/209,735 11 December 1998 (11.12.98) US (71) Applicant: STEAG RTP SYSTEMS GMBH [DE/DE]; Daimlerstrasse 10, D-89160 Dornstadt (DE). (72) Inventors: ASCHNER, Helmut; Kirchgasse 5, D-89179 Beimerstetten (DE). HAUKE, Andreas; Fasanenweg 4, D-89231 Neu-Ulm (DE). WEBER, Karsten; Gartenstrasse 52-1, D-71397 Leutenbach (DE). ZERNICKEL, Dieter; Donautalstrasse 57, D-89075 Ulm (DE).		(81) Designated States: JP, KR, SG, European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report. Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>
(54) Title: GAS DRIVEN ROTATING SUSCEPTOR FOR RAPID THERMAL PROCESSING (RTP) SYSTEM (57) Abstract An apparatus for preventing warping of a rotatable base for supporting an object being processed in a Rapid Thermal Processing (RTP) system due to non uniform heating of the base by radiation from the object being processed is disclosed.		